

**Photo-induced negative differential resistance and carrier-transport mechanisms
in the $\text{Bi}_2\text{FeCrO}_6$ resistive switching memory devices**

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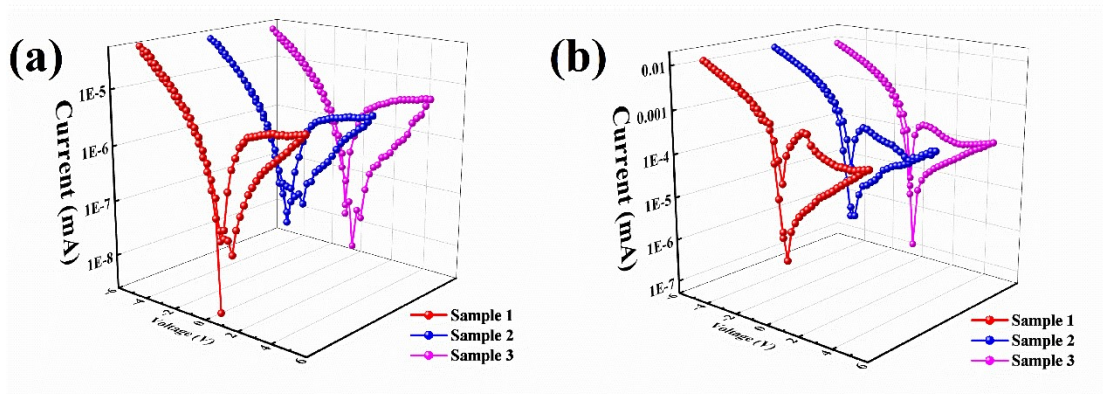


Fig. S1 The I - V cycle characteristic curves (-5.0 V to 5.0 V) of different Au/BFCO/FTO device: (a) in the dark and (b) under light-illumination.

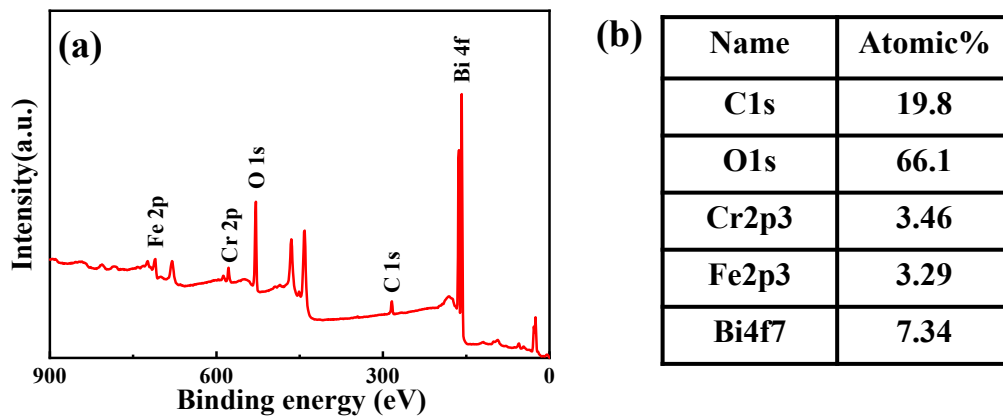


Fig. S2 (a) The XPS characteristic spectrum of BFCO film. (b) The atomic ratio of the Bi, Fe, and Cr of the BFCO thin film.

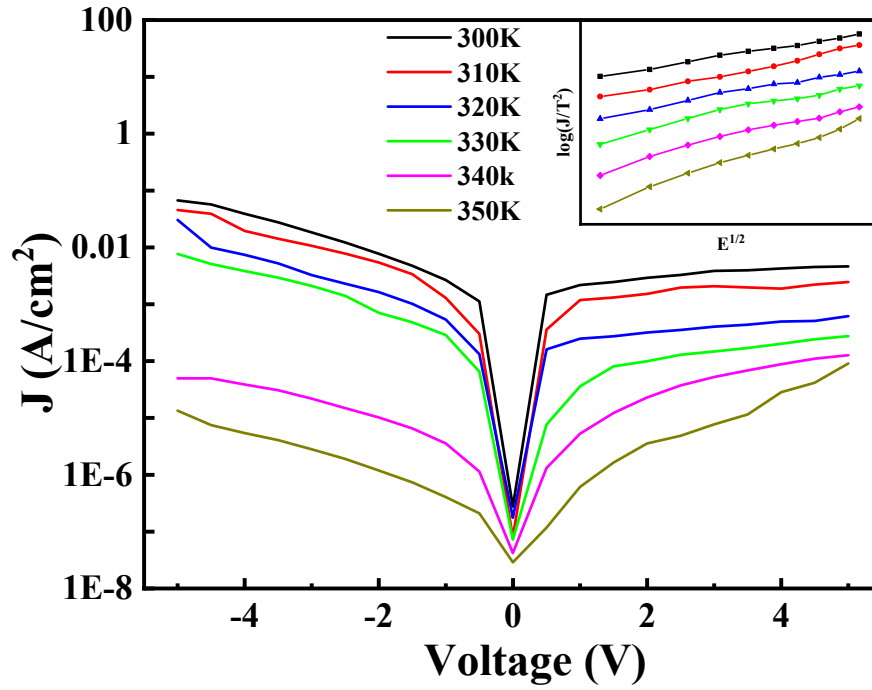


Fig. S3 J - V curves and $\log(J/T^2)$ - $E^{1/2}$ of Au/BFCO/FTO devices at different temperatures

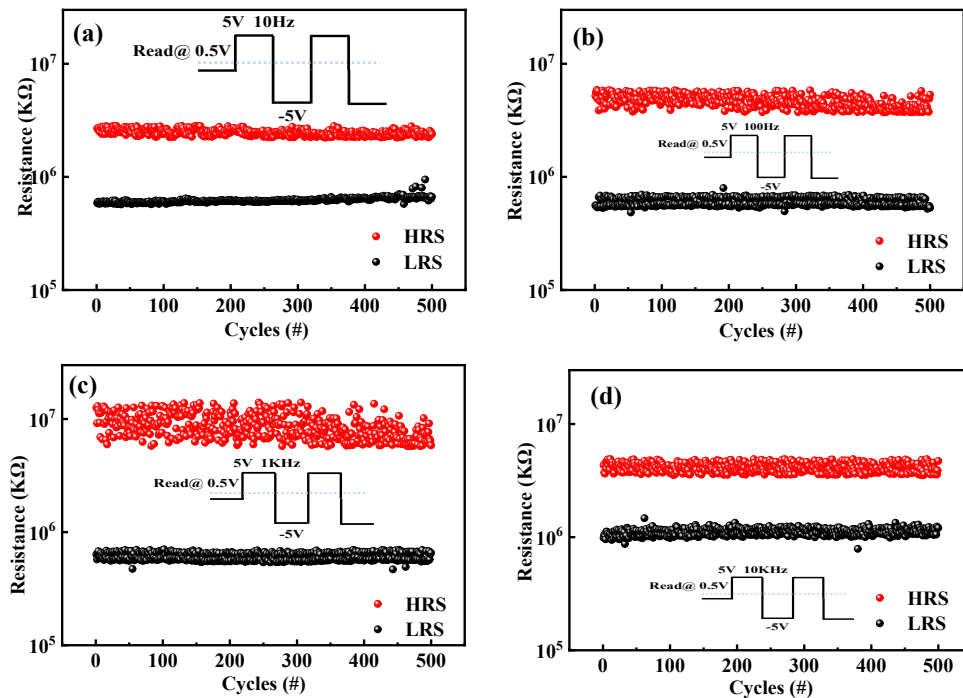


Fig. S4 RS of pulse signals of different frequencies: (a) 10 Hz, (b) 100 Hz, (c) 1K Hz, and (d) 10K Hz